

Title (en)

PHOTORESIST STRIPPING PROCESS USING N,N-DIMETHYL-BIS(2-HYDROXYETHYL) QUATERNARY AMMONIUM HYDROXIDE.

Title (de)

PHOTOLACKENTSCHICHTUNGSVERFAHREN MITTELS N,N-DIMETHYL-BIS (2-HYDROXYETHYL) QUATERNÄREN AMMONIUM HYDROXIOL.

Title (fr)

PROCEDE D'ELIMINATION D'AGENTS PHOTORESISTANTS EMPLOYANT DU M,M-DIMETHYLE-BIS(2-HYDROXYETHYLE) HYDROXYDE D'AMMONIUM QUATERNAIRE.

Publication

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Application

EP 93921680 A 19930923

Priority

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- US 95211292 A 19920928

Abstract (en)

[origin: WO9408276A1] A process for stripping photo-resists and an aqueous bath for use in the process are disclosed. The process is carried out at 40 to 100 C for about 0.1 to 10 minutes. The aqueous bath contains 1 to 10 weight percent N,N-dimethyl-bis(2-hydroxyethyl) quaternary ammonium hydroxide and preferably 0.5 to 10 weight percent of a metal complexing agent such as monoethanol amine, ethylene diamine, ethylene diamine tetraacetic, melamine, nitrilotriacetic acid, morpholine, acetonylacetone, and preferably from 0.1 to 5 weight percent ammonia.

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